

# EQ-10

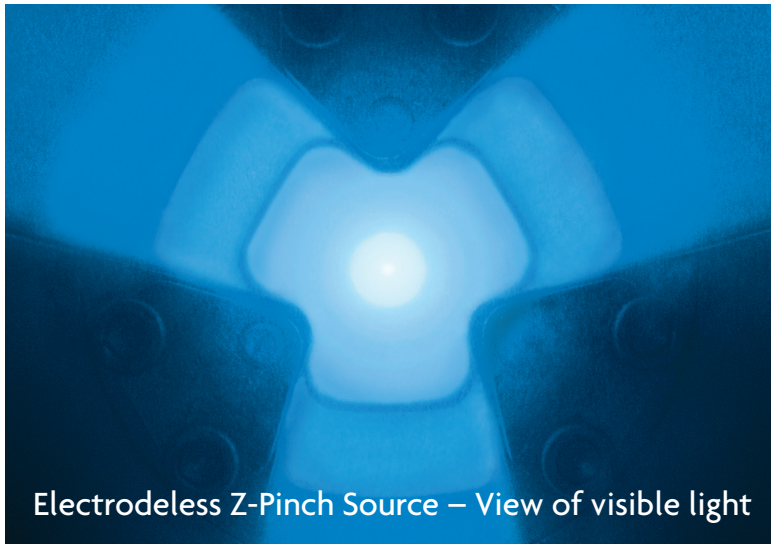
Compact, Reliable  
EUV Light Source



## Electrodeless Z-Pinch™ 10 Watt EUV Source

The EQ-10 is a compact, easy-to-use, reliable, and cost-effective light source, based on Energetiq's proven Electrodeless Z-Pinch™ technology using Xenon gas. The EQ-10 EUV source is uniquely suited for metrology and research applications. The EQ-10 has become the workhorse EUV source for the EUV community, through its proven reliability, ease of use, and low operating cost.

The Energetiq EQ-10 EUV Source's modular design makes it ready to be integrated in a process tool. The system includes the electrodeless Z-pinch source assembly, vacuum and gas subsystems, power delivery subsystem, and control electronics. The EQ-10 is capable of delivering up to 10 Watts of in-band EUV into  $2\pi$  steradians and will run continuously at pulse repetition rates of up to 2 kHz.



Electrodeless Z-Pinch Source – View of visible light

## Features and Benefits

- **Performance**
  - 10W into  $2\pi$  using Xenon
  - Up to 2 kHz pulse rate
  - Small plasma size
  - Low debris
- **Low Cost of Ownership**
  - Low Xenon flow rate
  - Minimized consumable cost
  - Small footprint
- **Proven Reliability**
  - Patented Electrodeless Z-Pinch™ technology
  - CE Mark and SEMI S2-0703 compliant

## Applications

- EUV Metrology
- EUV Resist Development
- EUV Inspection
- EUV Microscopy

# Electrodeless Z-Pinch™ Technology

Z-pinch plasmas have been shown to be effective at producing EUV and SXR light. However, all the implementations to date have involved conducting high discharge currents into the plasma using electrodes. These electrodes, which are typically in contact with high temperature plasma, can melt and produce significant debris.

Energetiq's unique technology is also based on a Z-pinch plasma, but it avoids electrodes entirely by inductively coupling the current into the plasma. The plasma in the Energetiq source is magnetically confined away from the source walls, minimizing the heat load and reducing debris. Energetiq's Electrodeless Z-Pinch™ technology has excellent spatial stability, and stable repeatable power output.

## Specifications

<b>EUV Performance</b>		
• EUV Power Output	10 Watts into $2\pi$ steradians (13.5 nm, $\pm 1\%$ bandwidth)	
• Pulse Repetition Rate	1200 to 2000 Hz	
• Source Operating Pressure	70 to 100 mTorr typical	
• Xenon Flow Rate	5 to 15 sccm typical	
<b>Physical Specifications</b>		
	<b>System Dimensions (H x W x D)</b>	<b>Weight</b>
• Instrument Rack	1356 x 611 x 915 mm (53.4 x 24.1 x 36.0 in)	215.5 kg (475 lbs)
• Modulator	498 x 356 x 701 mm (19.6 x 14.0 x 27.6 in)	54.4 kg (120 lbs)
• Source	764 x 556 x 533 mm (30.1 x 21.9 x 21.0 in)	95.3 kg (210 lbs)
• Fore Pump Assembly	643 x 259 x 460 mm (25.3 x 10.2 x 18.1 in)	27.7 kg (61 lbs)
<b>Utility Requirements</b>		
• Electrical	200–230V, 3 $\phi$ , 50/60 Hz, 30A	
• Cooling Water	40-60 PSID (0.28–0.41 MPa), 2.5gpm (9.5lpm) min., 30°C max. inlet	
• Clean Dry Air	75–90 PSIG (0.52–0.62 MPa)	
• Xenon	15–40 PSIG (0.10–0.28 MPa), 20 sccm max. (10 sccm typ.)	
<b>Compliance</b>		
• EQ-10 Series	CE Mark, SEMI S2-0703	

Patent Numbers: US 7,307,375; US 7,199,384; US 7,183,717; US 7,948,185; US 8,143,790; EP 2187711; Other patents applied for.

## About Energetiq

*Energetiq Technology, Inc. is a developer and manufacturer of advanced light sources that enable the analysis and manufacture of nano-scale structures and products. The Energetiq team combines its deep understanding of the high power plasma physics needed for high-brightness light generation with its long experience in building rugged industrial & scientific products. The result is that users can expect the highest levels of performance combined with the highest reliability.*



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Specifications are subject to change without notice.  
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